

Substitute for form 1449/PTO (Revised 07/2005) INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use as many sheets as necessary)				Complete if Known	
				Application Number	TO BE ASSIGNED 10/565034
				Filing Date	Concurrently Herewith
				First Named Inventor	Rouviere et al.
				Group Art Unit	2855
Examiner Name	Max Noori				
Sheet	1	of	1	Attorney Docket Number	033339/306516
OTHER DOCUMENTS					
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.			English Language Translation Attached
/MN/	1	PAILLOUX F. et al., "Stress relaxation in $c_{1-c_{11}}$ YBaCuO thin films on MgO substrate studied by LACBED", <i>Thin Solid Films</i> , Elsevier Switzerland, Vol. 368, No. 1, June 1, 2000, pp. 142-146.			YES
↓	2	LI B et al., "A Study of Residual Strain in a K20.6Ti02W/A1 Composite by Using Convergent Beam Electron Diffraction", <i>Scripta Materialia</i> , Elsevier, New York, NY, Vol. 38, No. 9, April 3, 1998, pp. 1419-1425.			YES
	3	ARMIGLIATO et al., "Application of Convergent Beam Electron Diffraction to Two-Dimensional Strain Mapping in Silicon Devices", <i>Applied Physics Letter</i> , American Institute of Physics, New York, Vol. 82, No. 13, March 31, 2003, pp. 2172-2174.			YES
	4	GAMBETTA F. et al., "Large angle convergent beam electron diffraction strain measurements in high dose helium implanted silicon", <i>Materials Science and Engineering B</i> , Elsevier Sequoia, Lausanne, CH, Vol. 71, No. 1-3, February 2000, pp. 87-91.			YES
	5	WAKAYAMA Y et al., "Strain Distribution Near Si/NiSi ₂ Interface Measured by Convergent Beam Electron Diffraction", <i>Japanese Journal of Applied Physics</i> , Publication Office Japanese Journal of Applied Physics, Tokyo, Japan, Vol. 35, Part 2, No. 12B, December 15, 1996, pp. L1662-L1665.			YES
	6	CLEMENT L et al., "Strain measurements by convergent-beam electron diffraction: the importance of stress relaxation in lamella preparations", <i>Applied Physics Letters AIP USA</i> , Vol. 85, No. 4, July 26, 2004, pp. 651-653.			YES
Examiner Signature	/Max Noori/			Date Considered	10/30/2007

*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.